





### Was bedeutet HiPIMS?





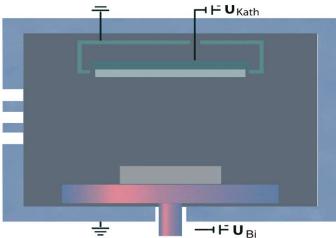
High
Power
Impuls
Magnetron
Sputtering

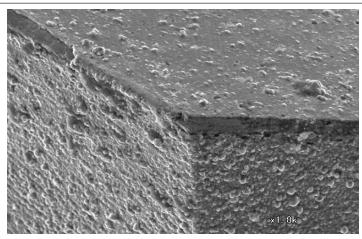
# ARC vs. **S**puttern?

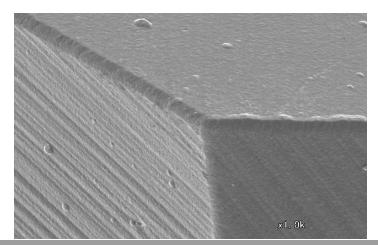












### Was kann HiPIMS?





Oberfläche	0	b	er	fl	ä	cl	h	е
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Beschichtungstemperatur

Max. Schichtdicke

Eigenspannungen der Schicht

Zähigkeit der Schicht

**Einfache Produktion** 

Flexibilität

Miniwerkzeuge

#### Arc

**Droplets** 

500 °C

4 µm

**Hohe Druckspannungen** 

Hoch

Ja

Geringe

Nein

#### CVD

Rau

1000 °C

10-15 μm

Zugspannungen

**Niedrig** 

Nein (Präkursor)

Keine

Nein

#### **HiPIMS**

Glatt

500 °C

12 µm

Niedrige Druckspannungen

Sehr hoch

Ja

**Hoch** (alle Materialien, alle Substrate)

Ja

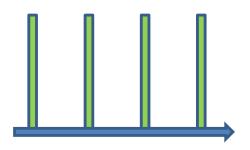
#### Wie funktioniert HiPIMS?







HiPIMS = kurze Hochenergiepulse



- Bias Synchronisation
- HiPIMS (ohne Kabel)
- = Gesamte Leistung in das Plasma

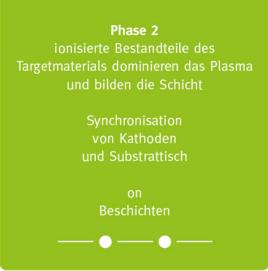
#### Wie funktioniert HiPIMS?











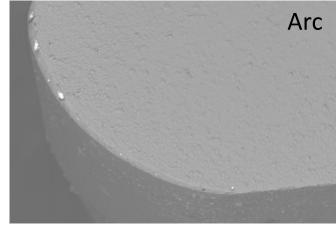


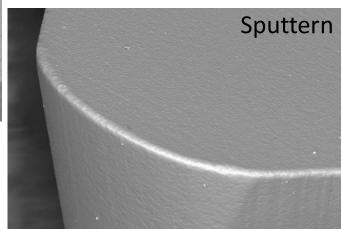
# Eigenspannungsmanagement

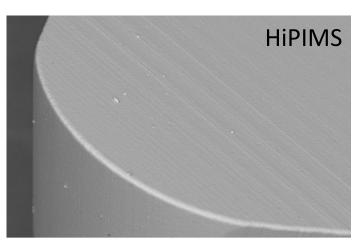
# Eigenspannungen









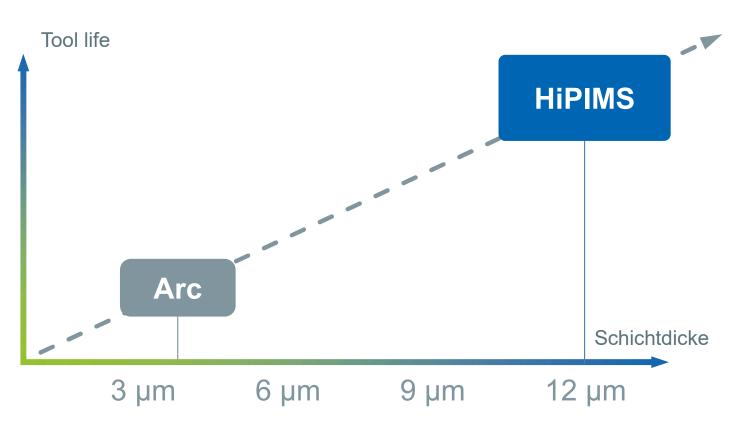


### HiPIMS – dicke Schichten in Serie





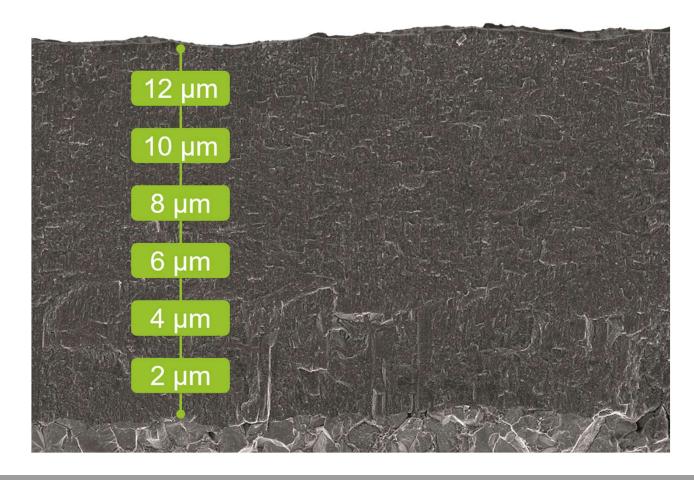




### HiPIMS – dicke Schichten in Serie







# HiPIMS - AITiSiN → Hartbearbeitung







sehr hoher Si Gehalt

glatt, 100% frei von Droplets beste Haftung

dichte Schicht

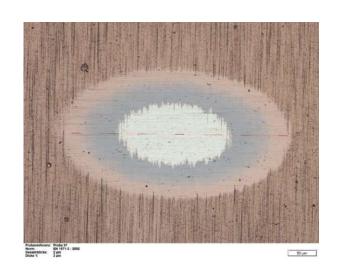
perfekt angepasste Eigenspannungen

## HiPIMS - AITISIN





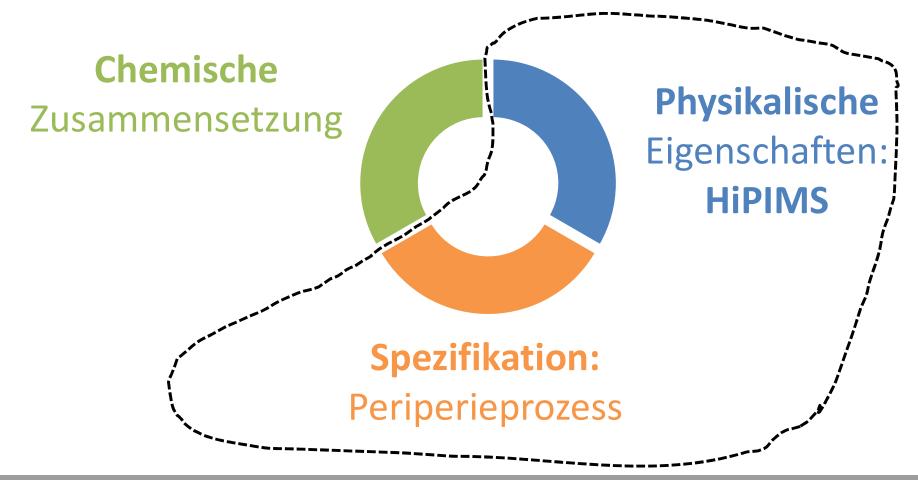




# HiPIMS - angepasst an das Werkzeug



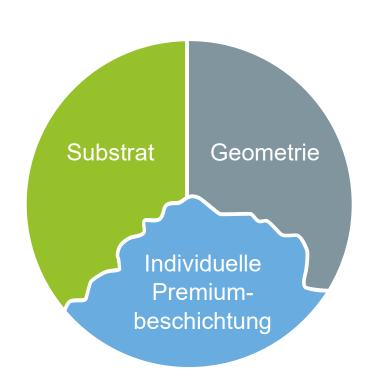




# ...angepasst an das Werkzeug









# Vorbehandlung







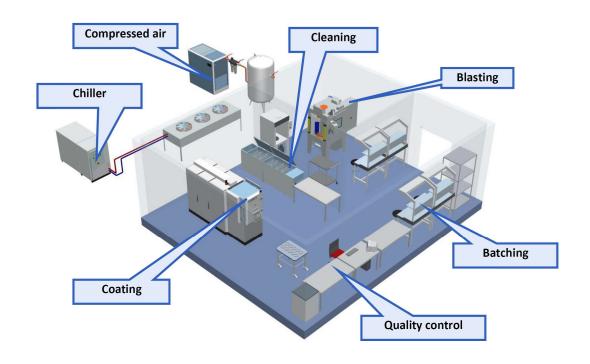
Eingangszustand

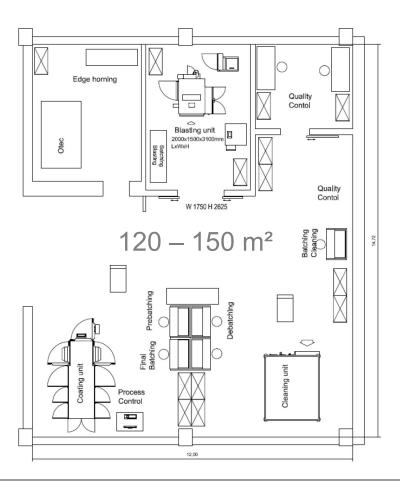
Nach dem Nassstrahlen

# Beschichtungszentrum







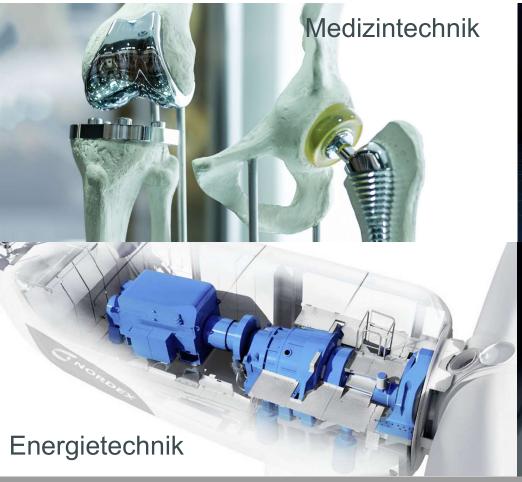




### Wachsende Märkte





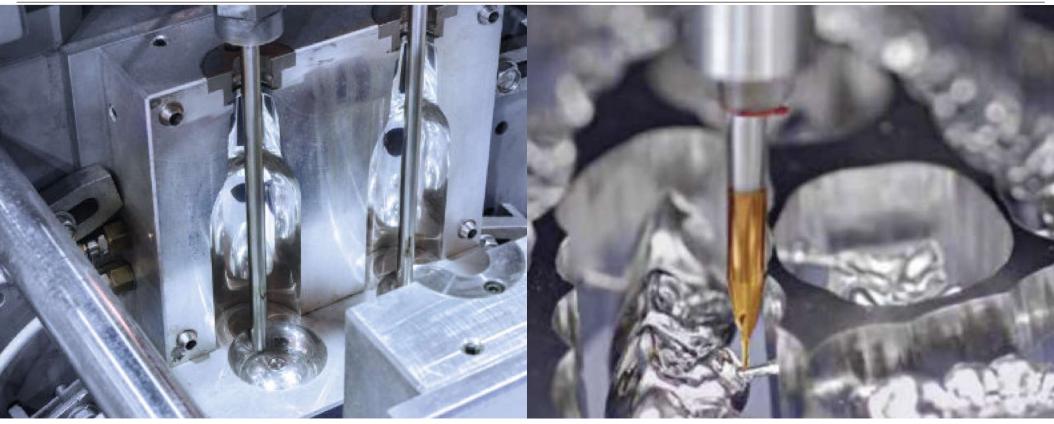




## HiPIMS - AITISIN







60 HRC - Formenbau

CrCo - Medizintechnik

#### HiPIMS: Wirtschaftlichkeit





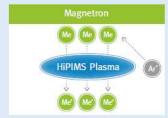




## Zusammenfassung







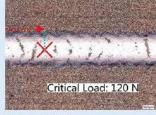
Nearly 100% metal ionization

The power peaks of HiPIMS result in an enormously dense plasma which provides an unrivalled degree of ionization to the deposited materials. The high flux of highly ionized species results in very dense and nearly amorphous coating structures.



Maximum flexibility

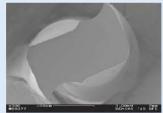
HiPIMS is a Sputter process. Almost every material can be sputtered. This means an unlimited variety of coatings through combinations of elements of the periodic system.



Highest adhesion

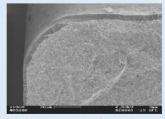
The high metal ionization ensures the best possible coating adhesion.

A scratch load of 120 Newton is an outstanding result for InoCon® as a silicon doped and thereby very hard coating. FerroCon®, based on AITiN, results in a scratch value of up to 130 Newton. This enables to machine the most difficult to cut materials.



Perfect for micro tools

Free of defects and without antenna effects. The HiPIMS technology is also very useful for very small geometries, as it works droplet-free and without damaging or rounding the cutting



Homogeneous coating all around the cutting edge

The high ionization makes the coating structure very dense and compact. Such a fine grain morphology is likewise hard and tough. Coatings grow extremely homogeneous when HiPIMS is used for the deposition.

Also, very complex tool geometries will receive approximately the same coating thickness all around the cutting edge.



Maximum profitability for pure HiPIMS coatings

The CC800® HiPIMS achieves in pure HiPIMS mode deposition rates of 2 µm/h and process times of 4-5 hours. 3 µm/h are possible when all 6 cathodes are used.





#### Vielen Dank für Ihre Aufmerksamkeit...

